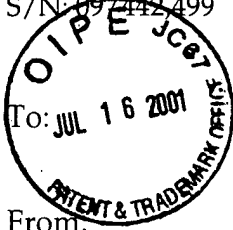


Docket: CS 99 - 065
S/N: 09/442,499



Commissioner of Patents and Trademarks
Washington, D.C. 20231

From:

George O. Saile, Reg. No. 19,572
20 McIntosh Drive
Poughkeepsie, N.Y. 12603

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JUL 18 2001

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Handwritten signatures and initials, including "H/B" and "2/19/01".

Subject:

Serial No. 09/442,499	Filed: 11/18/99
Inventor: Ho	
Title: Plasma Etch Method For Forming Plasma Etched Silicon Layer	
Group Art Unit: 1763	Examiner: Goudreau, B.
Attorney Docket: CS 99 - 065	

RESPONSE TO PATENT OFFICE ACTION

Dear Sir:

In response to the office action dated 05/11/01, please consider the following remarks:

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patent and Trademarks, Washington, D.C. 20231, on

July 11, 2001.

Signature/Date

George O. Saile 7/11/01
George O. Saile, Reg#19,572

07/17/2001 KZWDIE 00000009 190033 09442499

01 FC:103 144.00 CH
02 FC:102 240.00 CH